Special Issue

Application of Machine Learning in Data Analysis and Process

Message from the Guest Editor

ML techniques, including predictive analytics, anomaly detection, natural language processing, image analysis, recommendation systems, and process optimization, offer valuable capabilities that complement traditional statistical modeling approaches. The integration of ML with data analysis and processing offers a powerful approach to extract insights, make accurate predictions, and optimize processes. The continuous advancement of ML holds immense potential for unlocking deeper insights, driving data-driven decision making, and addressing the challenges posed by complex and evergrowing datasets. Keywords

machine learning; data analysis; data processing; predictive analytics; anomaly detection; natural language processing; image analysis; recommendation systems; process optimization; statistical modeling

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